

Time-Dependent Electrical Resistance of Transmutational Material With ^{57}Co

Norimasa Yoshimizu

Abstract—Transmutational material is studied as a changing electrical resistance over time. A process compatible to complementary metal oxide semiconductors is developed to deposit transmutational material. The material contains the radioisotope ^{57}Co which decays and causes an elemental change, in turn causing a change in electrical resistance over time. Significant increases—nearly a factor of four—in sample resistance over time are observed. Scaling is presented to show that samples that are less than 10 % of typical background exposure could be fabricated on the scale of microelectronics, avoiding detection. Finally, an application is demonstrated of a Wheatstone bridge containing a transmutational sample, leading to timed disabling of a power regulator.

Index Terms—Radioactive materials, time measurement, transmutation.

I. INTRODUCTION

THE use of radioactive materials in technological applications is typically designed to exploit their energetic emissions, such as due to their alpha or beta particles, or gamma rays. Nuclear batteries utilize the heat generated by the radioactive decay and convert it into electrical energy or, more directly, collect charged particles onto capacitive plates [1], [2] or generate electron-hole pairs in semiconducting materials [3]. For time measurement, a radioactive counting clock was reported which counted the beta radiation emitted by ^{63}Ni on an avalanche photodetector [4]. The use of radioisotopes in time measurement is predominated by radiocarbon dating [5]. Radiocarbon dating takes advantage of the decay of ^{14}C into ^{14}N where the relative presence of radioactive ^{14}C is used to determine the age of a sample.

Radiocarbon dating in particular takes advantage of an important distinction in the radioactive decay process. A radioisotope that undergoes decay experiences two distinct effects. First, alpha, beta, or gamma radiation is emitted, helping stabilize the atom. This is the effect used in most of the technologies described above. Second, the nucleus itself usually undergoes change in its atomic element, also called nuclear transmutation. In radiocarbon dating, the radioactive carbon atoms transmute into nitrogen atoms and thus occur

in lower concentrations as time passes. This transmutational effect is used less often in radioisotope applications but offers a unique capability. This paper reports on a study of transmutational material over time and its possible applications. It will show that transmutational material exhibits time-dependent resistivity that can be used for autonomous time measurement, specifically demonstrating a Wheatstone bridge circuit that triggers a timed disabling of a power regulator.

As a radioactive material transmutes over time, the changing elemental composition will cause related changes in bulk properties such as electrical resistance. There have been previous investigations of changes in electrical resistivities in radioactive materials. King et al. studied the changes in resistivity due to self-damage of plutonium, neptunium, and uranium showing resistivity changes of up to $3.5\times$ at 4.5 K [6]. Johnson et al. showed time-dependent changes in resistivity of neutron-irradiated CdS [7], [8]. Müller et al. showed up to $7\times$ net increase in electrical resistivity of ^{241}Am over time [9]. Finally, Rohrlack et al. implanted the radioisotopes ^{67}Ga and ^{71}As into GaAs, generating acceptor and donor sites and observing up to $2.5\times$ change in sheet resistivity [10]. The application of neutron irradiation and subsequent generation of transmutational material is similar to neutron transmutation doping, a technique where dopants can be introduced into semiconducting material more uniformly than thermal or ion beam techniques [11]. These previous studies, except the latter, involved techniques not chosen for making transmutational materials in technological applications. For example, designing an electronic system then irradiating it to generate radioactive material would also generate excess radioactivity, such as within the substrate and surrounding areas. Subsequently etching a thin film as part of a microfabrication process would generate unused radioactive waste material as well, increasing cost and fabrication complexity.

II. SAMPLE PREPARATION

This paper investigates transmutational material deposited directly onto a substrate by plating methods. Since the material is plated, the radioactive material can be selectively deposited. This isolates the radioactive material to where it is desired and increases the concentration that can be achieved, reducing the total activity that needs to be used. The process developed in this paper is also compatible to complementary metal oxide semiconductors (CMOS), requiring low temperatures. In particular, we study the deposition of ^{57}Co , a radioisotope

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which decays into Fe with a half-life of 272 days. The decay scheme of ^{57}Co proceeds by electron capture, resulting in the excited $J = 5/2^-$ state of Fe at 136 keV above the ground state and typically (88 % probability) emitting 122 keV photons and some subsequent, low energy electrons [12]. Cobalt 57 is commercially available at high specific activity, even at its maximum specific activity of 8500 Ci/g at the time of lot production. These characteristics make ^{57}Co a suitable, practical candidate for producing transmutational material that has the necessary change in resistance with minimal activity and detectability at low cost.

Samples were prepared using high specific activity of ^{57}Co using an electroless plating process developed based on earlier work [13], [14]. The radioactive solutions used were approximately 72 % of maximum specific activity (6,120 Ci/g). The electroless plating solution with radioactive ^{57}Co was a 0.1 M HCl solution containing CoCl_2 . The pH of the solution was adjusted by adding NaOH then evaporating off some water, resulting in a pH of 1.1. The substrate was bulk 1 cm \times 2 cm aluminum masked with 2.5 mil-thick Kapton tape with a 0.5 mm \times 0.5 mm opening for cobalt deposition and a 0.75 mm \times 0.75 mm opening for substrate contact. The substrate was maintained at 120 $^\circ\text{C}$. A micropipette was used to deposit 1 μL of solution at a time. The solution, after each deposit, leaves behind visible, solid crystals of NaCl which are removed in water. In total, 1 mCi are deposited per sample.

The plating of cobalt onto aluminum was confirmed by studying the equivalent, non-radioactive deposition process. At each step during drop-by-drop deposition, the solution dries and leaves behind solid NaOH. When the cobalt is depositing onto the aluminum substrate, the NaOH dries white in color. However, when cobalt is not depositing onto the aluminum and remains in the solution, the NaOH will dry with the light blue color characteristic of anhydrous CoCl_2 . In addition, comparing deposition with and without CoCl_2 shows obvious, visual differences on the substrate. Deposition with CoCl_2 results in a dark substrate surface whereas deposition without it retains a shiny, metallic appearance. Finally, energy dispersive X-ray spectroscopy measurements on a Tescan Mira3 field emission scanning electron microscope show the presence of significant amounts of cobalt on the substrate.

Table I shows the ratio of atomic concentrations of cobalt to aluminum and the same ratio per μL of deposition volume. There is a significant increase in the concentration of cobalt relative to aluminum, but it remains fairly constant per volume of solution. The deposition of radioactive cobalt was also confirmed by the radioactivity measured on the samples using a gamma detector. Control samples using the non-radioactive deposition process were also used to confirm that no changes in resistance are seen over time.

III. SAMPLE MEASUREMENT

The transmutational samples were measured directly through wires that were attached by conductive epoxy onto the ^{57}Co deposition area and the substrate; see Fig. 1. A source meter was used to perform a four-point measurement of the resistance through the samples at 10 mA of current.

TABLE I
ELEMENTAL CONCENTRATIONS OF COBALT DEPOSITION SAMPLES

Deposition solution volume (μL)	Ratio of atomic concentrations, Co/Al	Ratio of atomic concentrations, Co/Al, per volume of solution
3	9.2 %	3.1 %/ μL
6	15.2 %	2.5 %/ μL
9	42.3 %	4.7 %/ μL
12	43.9 %	3.7 %/ μL
15	95.3 %	6.4 %/ μL
18	99.1 %	5.5 %/ μL

Atomic concentrations of cobalt on $0.5 \times 0.5 \text{ mm}^2$ area of aluminum substrate after deposition, as measured by energy dispersive X-ray spectroscopy.

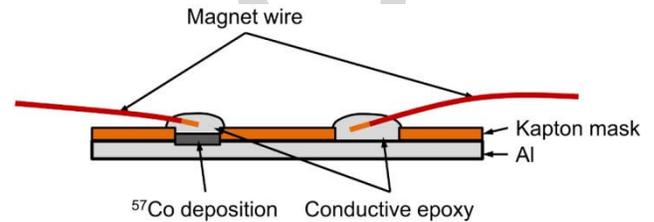


Fig. 1. Setup for resistance measurement of transmutational material. A Kapton tape mask was used to mask the deposition of ^{57}Co onto an Al substrate. Conductive silver epoxy was used to connect magnet wires to the substrate.

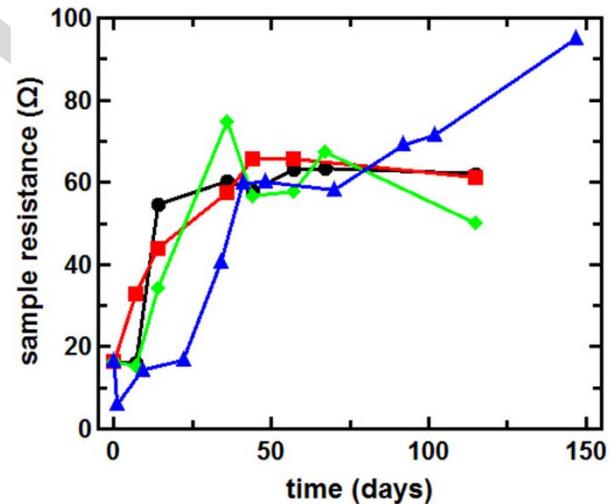


Fig. 2. Time-dependent resistance of four samples, showing data after series resistance is removed then scaled so that initial resistances are equal to the unadjusted curve depicted with red squares.

The measurements of the transmutational samples are shown in Fig. 2.

The raw data used for Fig. 2 showed variation among the four samples. Note that the blue curve has different sampling days as it was tested in a separate fabrication and test run. The initial resistances of the samples varied from 7.4 Ω to 21.8 Ω due to two main causes. First, there is variation in the series resistance to the sample incurred by the substrate, silver epoxy, and magnetic wires. Second, there is variation caused by the

149 deposition process. Only about 160 ng of ^{57}Co are deposited
 150 per sample along with 62 ng of nonradioactive isotopes of Co.
 151 The film is not contiguous and its effect on total sample
 152 resistance will vary based on its concentration across the
 153 sample. For example, a deposition whose coverage is sparse
 154 or thin will contribute smaller changes in resistance, whereas
 155 deposition that is both even and thicker will contribute larger
 156 changes. Therefore, the total sample resistance of a sample is
 157 assumed to be,

$$R_{\text{total}}(t) = R_0 + \alpha R_{\text{trans}}(t) \quad (1)$$

159 where R_0 is the series resistance due to the substrate, sil-
 160 ver epoxy, and magnet wires, and α scales the resistance
 161 $R_{\text{trans}}(t)$ of the transmutional film due to deposition process
 162 variations.

163 Fig. 2 shows the data after removing these variations.
 164 The data depicted in red squares is unchanged. The other
 165 data curves were generated by removing an offset, thereby
 166 removing the constant R_0 in Eq. 1, then scaling with a
 167 multiplicative constant so that the initial resistances all match
 168 at 16.3 Ω . The offset parameters are adjusted so that each
 169 data curve best matches the data depicted by the red squares
 170 by minimizing the mean squared error. The resulting curves
 171 show significant increase in resistance by a factor of 3.8 ± 0.4
 172 after only 42% of half-life has passed.

173 IV. DISCUSSION

174 The data show that large changes in resistance can be
 175 generated in transmutional samples, implying that very small
 176 radioactivity could be used in many applications. Doing so
 177 reduces the risk to human and environmental health, cost,
 178 and detectability of the radioactive material. In a clandestine
 179 application, it is desirable to prevent the detection of trans-
 180 mutational material using radiation detectors. Therefore, we
 181 consider as a stringent limit on radioactivity a level which
 182 would be difficult to distinguish from background. For ^{57}Co ,
 183 a gamma emitter, typical background for a gamma detector is
 184 10 $\mu\text{R/hr}$. We take as a limit of detectability ten percent of
 185 background, or 1 $\mu\text{R/hr}$. We assume that the exposure from
 186 a ^{57}Co source is primarily due to its 122 keV gamma rays
 187 and use typical physical parameters: ion generation in air at
 188 33.8 eV per pair, X-ray mass attenuation coefficient in dry air
 189 at 122 keV of $2.4 \times 10^{-2} \text{ cm}^2/\text{g}$, a detector with a 1 cm radius,
 190 and a distance of 2.54 cm between the radioactivity and the
 191 detector. As a result, 11 nCi of ^{57}Co generates an exposure
 192 of 1 $\mu\text{R/hr}$ at a distance of 2.54 cm. Using the gamma ray
 193 dose constant of 0.151 rem/hr/Ci at one meter yields a dose
 194 of 2.6 $\mu\text{ rem/hr}$ at 2.45 cm and, for comparison, the U.S.
 195 Nuclear Regulatory Commission exempt quantity for ^{57}Co is
 196 100 $\mu\text{ Ci}$, or about 10,000 times more activity than a single,
 197 11 nCi transmutional device [15].

198 Fig. 3 shows the scaling of device geometries by reducing
 199 device radioactivity using ^{57}Co . The range of areas and thick-
 200 ness required for various radioactivities and specific activities
 201 are shown. Note that these dimensions are compatible with
 202 typical microfabrication parameters. The activities could be
 203 further decreased by reducing the specific activity and thus

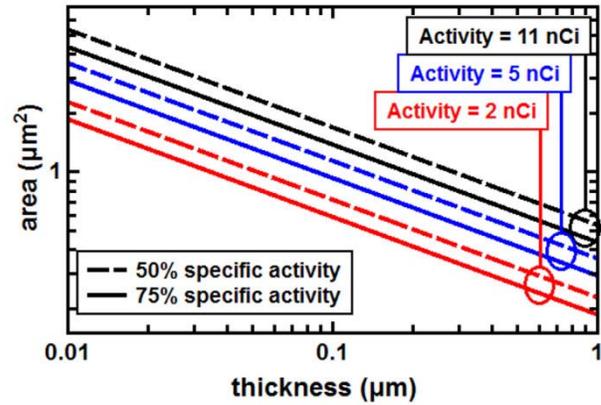


Fig. 3. Parameters for fabricating low activity devices using 50 or 75% specific activity ^{57}Co with dimensions of micrometers in width and hundreds of nanometers in thickness. Devices with activities of 2, 5, or 11 nCi are shown, where the latter generates about 1 $\mu\text{R/hr}$ at 2.54 cm for a typical gamma detector, or about 10% of background.

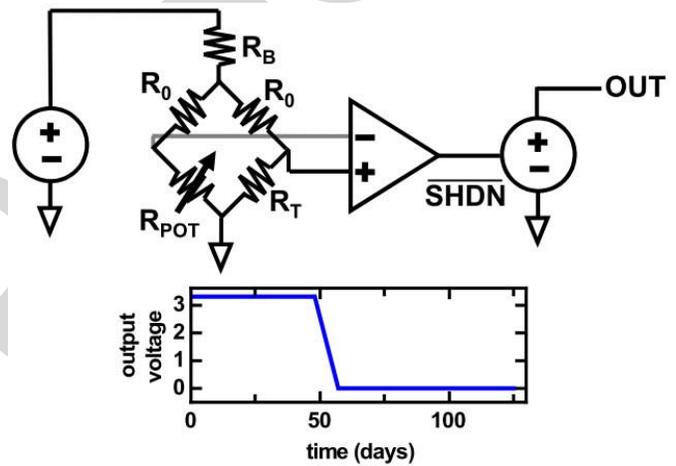


Fig. 4. Schematic of example application of transmutional material, where a Wheatstone bridge triggers a signal to shut down a power regulator. Data below shows output voltage from printed circuit board prototype over time.

204 reducing the net change in resistance as a tradeoff, as the
 205 data show that even small amounts of transmutionation can
 206 cause significant changes in resistance. In summary, it may
 207 be feasible to scale down the fabrication processes discussed
 208 in this paper to create micron and submicron-scale devices
 209 which are radiologically safe and very difficult to detect.

210 The use of transmutional properties may have advantages
 211 over other technologies where radioactive materials act as a
 212 timing mechanism. Measuring radioactive decay requires extra
 213 circuitry and significant activity to generate sufficient signal
 214 strength and particle counts to reach the required timing accu-
 215 racy. For comparison, a 1 mCi source of ^{57}Co only generates
 216 720 nW of energy. However, if a transmutional material can
 217 increase the series impedance of a device consuming 20 mA
 218 at 3.3 V by 20 Ω (12 %), the power delivered to the device
 219 would be reduced by 14 mW (21 %). Such changes can also be
 220 measured more easily and precisely by comparators or other
 221 differential circuits.

222 Applications which may benefit would be those that require
 223 an independent, self-powered, and time-dependent process.

224 Note that the transmutation process, due to its underlying
 225 physics, is largely unaffected by external electromagnetic,
 226 mechanical, or thermal forces and thus reliable and robust
 227 against many physical effects. In a simple application the
 228 resistance across a transmutational device could be used as a
 229 measurement of time. That measurement could be recorded or,
 230 if integrated into a circuit, used to cause failure or malfunction
 231 in an electronic device. Note that hardware Trojan taxonomies
 232 do not yet seem to include a classification for purely time-
 233 dependent attacks [16]. Fig. 4 shows such an example where
 234 a transmutational resistor was used to cause a power regulator
 235 to shut down after some time had passed. A Wheatstone
 236 bridge has a bias resistor R_B , constant leg resistances R_0 ,
 237 a transmutational resistor R_T , and an adjustable resistance
 238 R_{POT} which is set relative to R_T to define a time until
 239 shutdown of the regulator. The data at the bottom of Fig. 4
 240 is empirical data using a transmutational sample to cause a
 241 commercial 3.3 V power regulator to shut down after seven
 242 weeks.

243 V. CONCLUSION

244 This paper demonstrated a time-dependent resistor using
 245 transmutational material with a $3.8\times$ increase in resistance.
 246 A CMOS-compatible, selective deposition process was de-
 247 veloped. Scaling was studied to show compatibility with
 248 microelectronic geometries. Finally, an application involving
 249 a Wheatstone bridge used to trigger shutdown in a power
 250 regulator was demonstrated.

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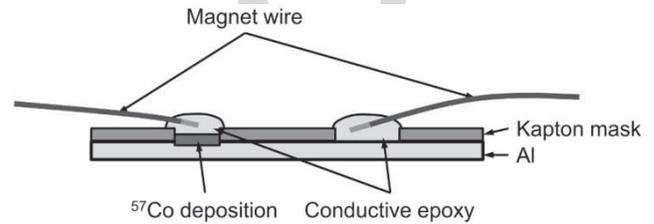


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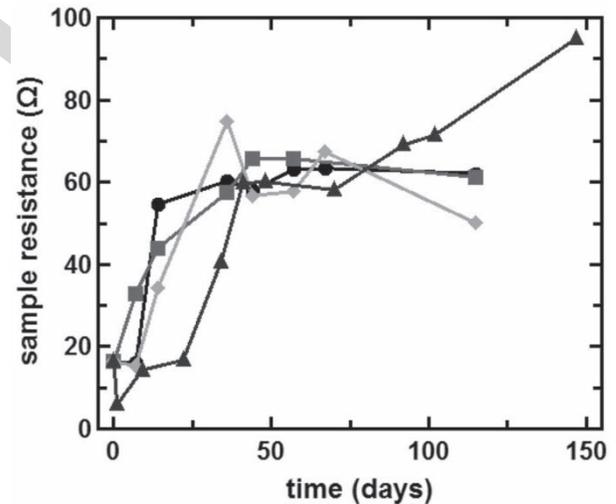


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 184 $10 \mu\text{R/hr}$. We take as a limit of detectability ten percent of
 185 background, or $1 \mu\text{R/hr}$. We assume that the exposure from
 186 a ^{57}Co source is primarily due to its 122 keV gamma rays
 187 and use typical physical parameters: ion generation in air at
 188 33.8 eV per pair, X-ray mass attenuation coefficient in dry air
 189 at 122 keV of $2.4 \times 10^{-2} \text{ cm}^2/\text{g}$, a detector with a 1 cm radius,
 190 and a distance of 2.54 cm between the radioactivity and the
 191 detector. As a result, 11 nCi of ^{57}Co generates an exposure
 192 of $1 \mu\text{R/hr}$ at a distance of 2.54 cm. Using the gamma ray
 193 dose constant of 0.151 rem/hr/Ci at one meter yields a dose
 194 of $2.6 \mu\text{ rem/hr}$ at 2.45 cm and, for comparison, the U.S.
 195 Nuclear Regulatory Commission exempt quantity for ^{57}Co is
 196 $100 \mu\text{ Ci}$, or about 10,000 times more activity than a single,
 197 11 nCi transmutional device [15].

198 Fig. 3 shows the scaling of device geometries by reducing
 199 device radioactivity using ^{57}Co . The range of areas and thick-
 200 ness required for various radioactivities and specific activities
 201 are shown. Note that these dimensions are compatible with
 202 typical microfabrication parameters. The activities could be
 203 further decreased by reducing the specific activity and thus

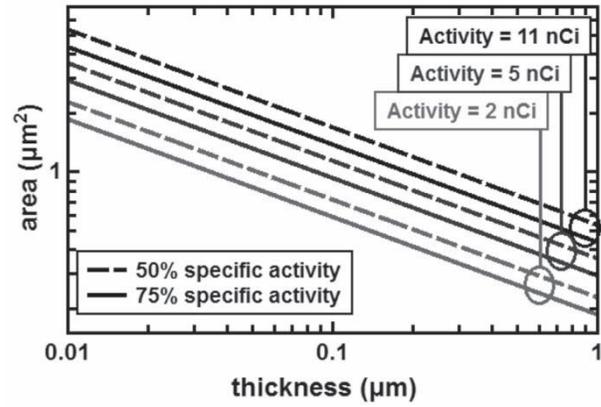


Fig. 3. Parameters for fabricating low activity devices using 50 or 75% specific activity ^{57}Co with dimensions of micrometers in width and hundreds of nanometers in thickness. Devices with activities of 2, 5, or 11 nCi are shown, where the latter generates about $1 \mu\text{R/hr}$ at 2.54 cm for a typical gamma detector, or about 10% of background.

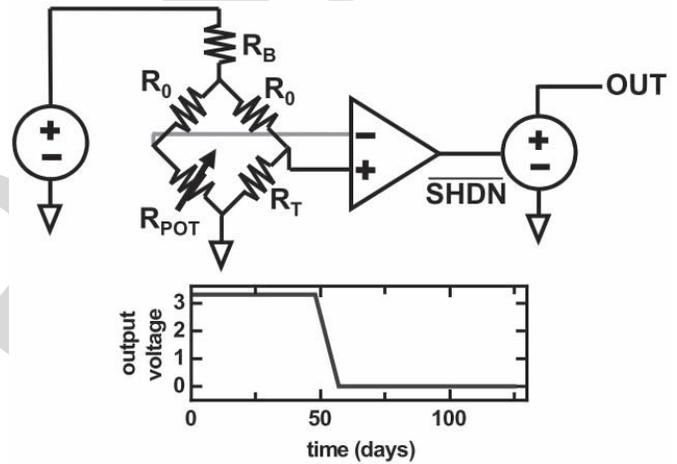


Fig. 4. Schematic of example application of transmutional material, where a Wheatstone bridge triggers a signal to shut down a power regulator. Data below shows output voltage from printed circuit board prototype over time.

204 reducing the net change in resistance as a tradeoff, as the
 205 data show that even small amounts of transmutionation can
 206 cause significant changes in resistance. In summary, it may
 207 be feasible to scale down the fabrication processes discussed
 208 in this paper to create micron and submicron-scale devices
 209 which are radiologically safe and very difficult to detect.

210 The use of transmutional properties may have advantages
 211 over other technologies where radioactive materials act as a
 212 timing mechanism. Measuring radioactive decay requires extra
 213 circuitry and significant activity to generate sufficient signal
 214 strength and particle counts to reach the required timing accu-
 215 racy. For comparison, a 1 mCi source of ^{57}Co only generates
 216 720 nW of energy. However, if a transmutional material can
 217 increase the series impedance of a device consuming 20 mA
 218 at 3.3 V by 20Ω (12%), the power delivered to the device
 219 would be reduced by 14 mW (21%). Such changes can also be
 220 measured more easily and precisely by comparators or other
 221 differential circuits.

222 Applications which may benefit would be those that require
 223 an independent, self-powered, and time-dependent process.

224 Note that the transmutation process, due to its underlying
 225 physics, is largely unaffected by external electromagnetic,
 226 mechanical, or thermal forces and thus reliable and robust
 227 against many physical effects. In a simple application the
 228 resistance across a transmutational device could be used as a
 229 measurement of time. That measurement could be recorded or,
 230 if integrated into a circuit, used to cause failure or malfunction
 231 in an electronic device. Note that hardware Trojan taxonomies
 232 do not yet seem to include a classification for purely time-
 233 dependent attacks [16]. Fig. 4 shows such an example where
 234 a transmutational resistor was used to cause a power regulator
 235 to shut down after some time had passed. A Wheatstone
 236 bridge has a bias resistor R_B , constant leg resistances R_0 ,
 237 a transmutational resistor R_T , and an adjustable resistance
 238 R_{POT} which is set relative to R_T to define a time until
 239 shutdown of the regulator. The data at the bottom of Fig. 4
 240 is empirical data using a transmutational sample to cause a
 241 commercial 3.3 V power regulator to shut down after seven
 242 weeks.

243 V. CONCLUSION

244 This paper demonstrated a time-dependent resistor using
 245 transmutational material with a $3.8\times$ increase in resistance.
 246 A CMOS-compatible, selective deposition process was de-
 247 veloped. Scaling was studied to show compatibility with
 248 microelectronic geometries. Finally, an application involving
 249 a Wheatstone bridge used to trigger shutdown in a power
 250 regulator was demonstrated.

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